

FS-F-1030/ 1~5 μ J/1-5W

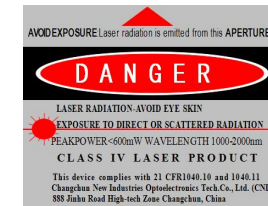
FEMTOSECOND PULSED LASER AT 1030nm

All Fiber Femtosecond pulsed laser at 1030nm is made features of short pulse duration, high repetition rate, high stability and good beam quality, which is used in sapphire marking, ceramic cutting, semiconductor cutting, film scribing, physics experiment, etc.

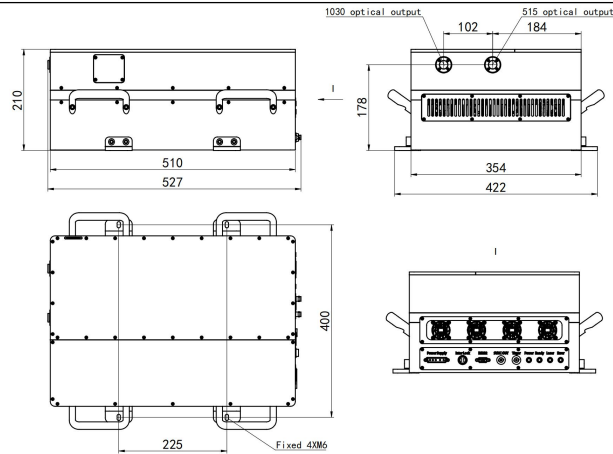


SPECIFICATIONS

Wavelength (nm)	1030±5
Average power (W)	5W (5W@1MHz)
Single pulse energy (μ J)	5(5 μ J @1MHz)
Rep. rate (MHz)	1MHz
Pulse duration (fs)	<300fs @1MHz,5W.
Peak power (MW)	14.3MW @1MHz
Ave power stability (over 4 hours)	<1%
Warm-up time (minutes)	<10
Transverse mode	TEM ₀₀
Beam quality(M ²)	<1.3
Beam divergence, full angle (mrad)	<1.0
Beam diameter at the aperture (1/e ² ,mm)	~2
Polarization ratio	>100:1
Beam height from base plate (mm)	178
Cooled method	Air cooled

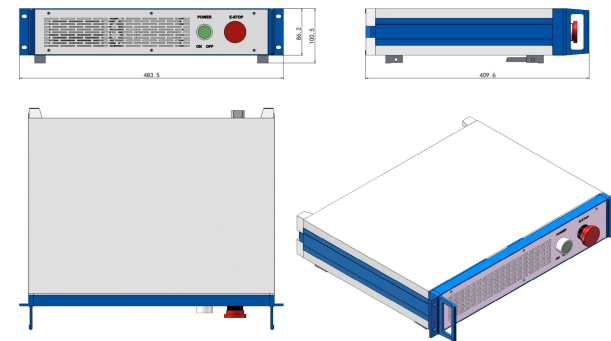


FS-F-1030-5W



510(L) × 354(W) × 210(H) mm³, 40 kg

Power supply



483.5 (L) × 409.6(W) × 100.5(H) mm³, 4.5 kg

FS-F-1030/10~50 μJ/10~20W

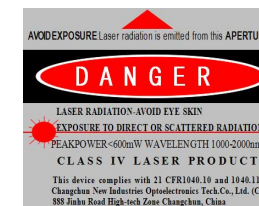
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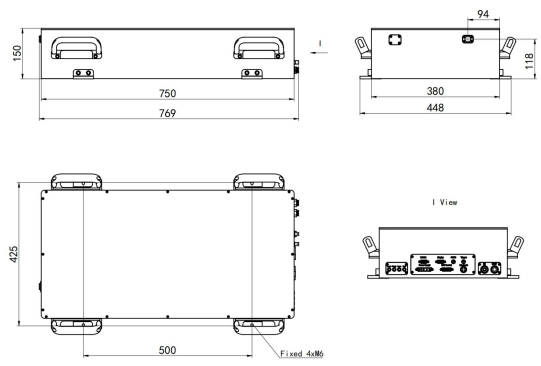
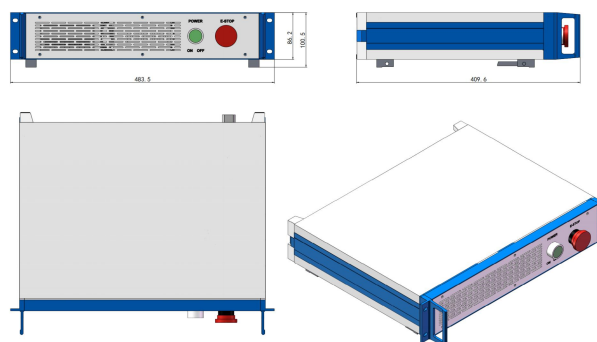
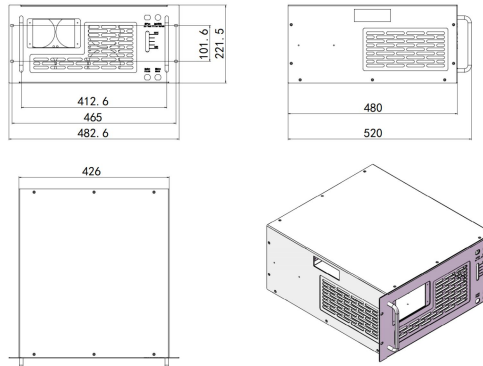
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SPECIFICATIONS

Wavelength (nm)	1030±5
Average power (W)	20 (20W@1MHz); 10(10W@200kHz)
Single pulse energy (μ J)	20 (20 μ J @1MHz); 50 (50 μ J @200kHz)
Rep. rate (MHz)	100kHz-1MHz
Pulse duration (fs)	<300fs or 300fs-10ps adjustable
Peak power (MW)	67MW @1MHz; 167MW@200kHz
Ave power stability (over 4 hours)	<1%
Warm-up time (minutes)	<10
Transverse mode	TEM ₀₀
Beam quality(M ²)	<1.2
Beam divergence, full angle (mrad)	<1.0
Beam diameter at the aperture (1/e ² ,mm)	~2
Polarization ratio	>100:1
Beam height from base plate (mm)	118
Cooled method	Water cooled
Operating temperature (°C)	15~35
Power supply (220/110VAC)	On request
Expected lifetime (hours)	10000
Warranty period	1 year



<p style="text-align: center;">FS-F-1030-20W</p>  <p style="text-align: center;">750(L) × 380(W) × 150(H) mm³, 50kg</p>	<p style="text-align: center;">Power supply</p>  <p style="text-align: center;">483.5 (L) × 409.6(W) × 100.5(H) mm³, 4.5 kg</p>	<p style="text-align: center;">Water Chiller</p>  <p style="text-align: center;">520(L) × 482.6(W) × 221.5(H) mm³, 25 kg</p>
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FS-F-1030/10~50 μJ/20~50W

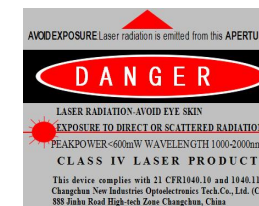
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SPECIFICATIONS

Wavelength (nm)	1030±5
Average power (W)	50 (50W@1MHz)
Single pulse energy (μ J)	50 (50 μ J @1MHz)
Rep. rate (MHz)	100kHz-1MHz
Pulse duration (fs)	<300fs or 300fs-10ps adjustable
Peak power (MW)	167MW @1MHz
Ave power stability (over 4 hours)	<1%
Warm-up time (minutes)	<10
Transverse mode	TEM ₀₀
Beam quality(M ²)	<1.2
Beam divergence, full angle (mrad)	<1.0
Beam diameter at the aperture (1/e ² ,mm)	~2
Polarization ratio	>100:1
Beam height from base plate (mm)	118
Cooled method	Water cooled
Operating temperature (°C)	15~35
Power supply (220/110VAC)	On request
Expected lifetime (hours)	10000
Warranty period	1 year



<p style="text-align: center;">FS-F-1030-50W</p> <p style="text-align: center;">750(L) × 380(W) × 150(H) mm³, 50kg</p>	<p style="text-align: center;">Power supply</p> <p style="text-align: center;">483.5 (L) × 409.6(W) × 100.5(H) mm³, 4.5 kg</p>	<p style="text-align: center;">Water Chiller</p> <p style="text-align: center;">520(L) × 482.6(W) × 221.5(H) mm³, 25 kg</p>
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FS-F-1030/50-200 μ J/ 50-100 W

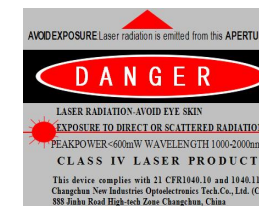
FEMTOSECOND PULSED LASER AT 1030nm

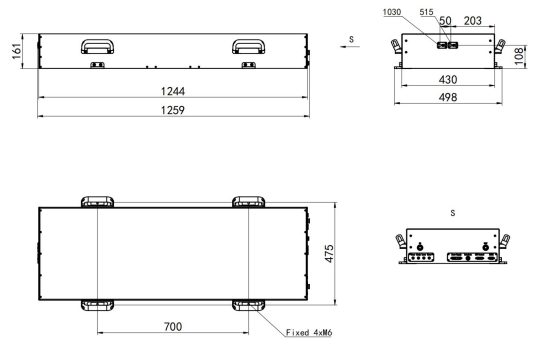
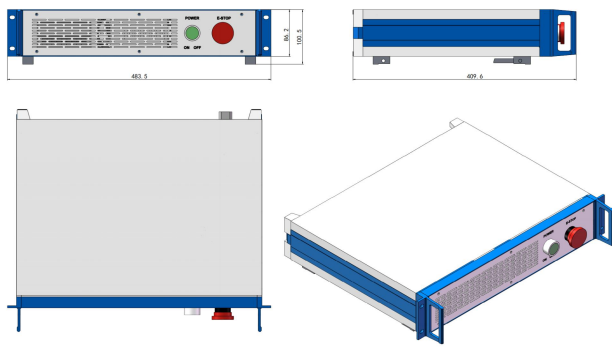
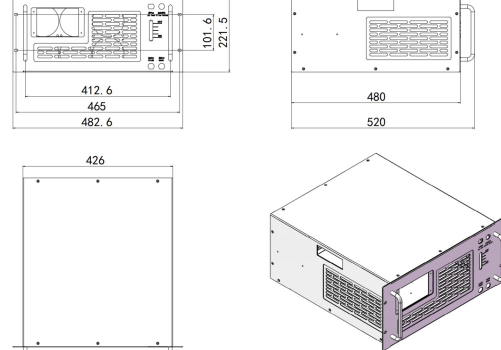
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SPECIFICATIONS

Wavelength (nm)	1030±5
Average power (W)	100 (100W@1MHz); 100(100W@500kHz)
Single pulse energy (μ J)	100 (100 μ J @1MHz); 200 (200 μ J @500kHz)
Rep. rate (MHz)	100kHz-1MHz
Pulse duration (fs)	<300fs or 300fs-10ps adjustable
Peak power (MW)	330MW @1MHz; 670MW@500kHz
Ave power stability (over 4 hours)	<1%
Warm-up time (minutes)	<10
Transverse mode	TEM ₀₀
Beam quality(M ²)	<1.3
Beam divergence, full angle (mrad)	<1.0
Beam diameter at the aperture (1/e ² ,mm)	~3
Polarization ratio	>100:1
Beam height from base plate (mm)	108
Cooled method	Water cooled
Operating temperature (°C)	15~35
Power supply (220/110VAC)	On request
Expected lifetime (hours)	10000
Warranty period	1 year



FS-F-1030-100W	Power supply	Water Chiller
 <p>1244(L) × 430(W) × 161(H) mm³, 90kg</p>	 <p>483.5 (L) × 409.6(W) × 100.5(H) mm³, 4.5 kg</p>	 <p>520(L) × 482.6(W) × 221.5(H) mm³, 25 kg</p>